

Abstract

In a manufacturing method in which a source line is provided around a pixel electrode provided on a substrate, an insulating film having open regions that will provide a source and a gate is formed, the source and the drain are formed, and a semiconductor film and a gate are provided on the source and drain, the above constituents are formed substantially under atmospheric pressure. Since manufacture can be accomplished substantially under the atmospheric pressure, no special apparatus, such as a vacuum chamber, is required, permitting a display device to be manufactured at lower cost.